

**● PRINTER RUSH ●**  
(PTO ASSISTANCE)

FFW

Application : 10/714829 Examiner : Hoang GAU : 2818

From : TW Location: IDC FMF (FDC) Date: 4-3-06

Tracking #: 6125998 Week Date: 7-18-07

DOC CODE	DOC DATE	MISCELLANEOUS
<input type="checkbox"/> 1449		<input type="checkbox"/> Continuing Data
<input type="checkbox"/> IDS		<input type="checkbox"/> Foreign Priority
<input type="checkbox"/> CLM		<input type="checkbox"/> Document Legibility
<input type="checkbox"/> IIFW		<input type="checkbox"/> Fees
<input type="checkbox"/> SRFW		<input type="checkbox"/> Other
<input type="checkbox"/> DRW		
<input type="checkbox"/> OATH		
<input type="checkbox"/> 312		
<input checked="" type="checkbox"/> SPEC	<u>11-14-02</u>	

**[RUSH] MESSAGE:**

The specification submitted on 11-14-02 does not contain a paragraph  
referring to color drawings as required per 37 CFR 1.84 (A)(2)(iv).

Please correct the specification

Thank You  
TW

**[XRUSH] RESPONSE:**

Corrected.

INITIALS: JBH

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REV 10/04

device of the display area in the liquid crystal display or the like, it is possible to form a display with excellent display quality.

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#### BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 is a view explaining a conventional positional relationship between a substrate to be processed and a region to be irradiated by a line beam.

10 FIG. 2 is a view showing a planar construction of a TFT formed by a conventional laser anneal.

FIG. 3 is a graph explaining an energy profile of an irradiation laser beam.

15 FIG. 4 is a view explaining a positional relationship between a substrate to be processed and a region to be irradiated by a line beam according to an embodiment of the present invention.

FIGS. 5, 6, 7 and 8 are graphs explaining an energy profile of a line beam according to an embodiment of the present invention.

20 FIG. 9 is a graph showing a relation between laser beam irradiation time (the number of pulse shots) and temperature of a film to be processed in the ELA according to an embodiment of the present invention.

25 FIG. 10 is a graph showing a relation between laser beam irradiation time (the number of pulse shots) and a grain size of a film to be processed in the ELA according to an embodiment of the present invention.

{ The patent or application file contains at least one drawing executed in color. Copies of this patent or patent application publication with color drawing(s) will be provided by the U.S. Patent and Trademark Office upon request and payment of the necessary fee.